

INFORMATION DISCLOSURE CITATION (Use several sheets if necessary)			Doctet Number (Optional) DE920000065US1	Application Number 10/614,545			
			Applicant(s) MARKUS SCHMIDT	Filing Date 7/07/03	Group Art Unit 2813		
U.S. PATENT DOCUMENTS							
EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE
<i>TW</i>		5,837,426	11/17/1998	TSENG, ET AL.			
<i>TW</i>		6,042,993	03/28/2000	LEUSCHNER, ET AL.			
FOREIGN PATENT DOCUMENTS							
	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES NO
<i>TW</i>		EP104S291A3	10.01.2001	EUROPE			
<i>TW</i>		JP02257624 A2	18.10.90	JAPAN			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
<i>TW</i>		MicroElectroic Engineering "SENSITIVITY-ENHANCED DRY DEVELOPMENT PROCESS FOR VUV AND EUV LITHOGRAPHY USING GRAFT-POLYMERIZATION", 1996, PCS 287-290					
EXAMINER	<i>Clear</i>			DATE CONSIDERED <i>2/1/05</i>			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with any							

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